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Supporting Information for

High-performance broadband heterojunction photodetectors based on multilayered PtSe₂ directly grown on Si substrate

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Figure S1. Photographs of bare Si and PtSe₂/Si substrates.



Figure S2. (a) The statistical distribution of the ratio of the intensity of the two distinct peaks extracted from Raman spectra of $PtSe_2$ sample. (b) The statistical distribution of interlayer spacing of crystalline domains with (001) plane of $PtSe_2$ films.



Figure S3. (a) *I-V* characteristics of Au-PtSe₂-Au and In/Ga-Si-In/Si heterostructures, indicating good Ohmic contact between Au and PtSe₂ and In/Ga and Si, respectively. (b) Time-dependent photoresponse of PtSe₂/Si heterojunction photodetector during operation for over a thousand cycles.



Figure S4. *I-V* curves of PtSe₂/Si heterojunction photodetectors with PtSe₂ thicknesses of (a) ~2.5 nm, ~5 nm, (b) ~7.5 nm, 10.5 nm and 14.5 nm, in dark and under 808-nm NIR illumination (87.6 μ Wcm⁻²), respectively.



Figure S5. (a) *I-V* curves of heterojunction device under 808-nm illumination with light intensities of (a) 0.71 μ Wcm⁻²-0.267 mWcm⁻² and (b) 0.362 mWcm⁻²-13.93 mWcm⁻². (c) Time-dependent photoresponse of device under 1310-nm illumination (intensity: 5.50 mWcm⁻²).